Searc	h N	otes
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Application No.	Applicant(s)	_
09/912,398	INANAMI ET AL.	
Examiner	Art Unit	
Mary C Hogan	2123	

SEARCHED			
Class	Subclass	Date	Examiner
703	2,20	12/16/2004	мсн
700	105-107	12/16/2004	мсн
700	19,182	12/16/2004	мсн
716	21	12/16/2004	мсн
			-

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
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SEARCH NOT (INCLUDING SEARCH)
	DATE	EXMR
Inventor Name Search: EAST, IEEE	12/15/2004	мсн
IEEE: charged particle beam, character projection, semiconductor <and> manufacture <and> order <and> design <and> cost <and></and></and></and></and></and>	12/16/2004	мсн
ACM: character projection,manufacture, mask customer design	12/16/2004	мсн
IEEE: semiconductor <and> design <and> 'real time' <and> network</and></and></and>	12/16/2004	мсн
EAST:character projection,circuit pattern,specification,parameter,cost,ti me,network,charged particle beam,mask,aperture,order	12/16/2004	мсн